

Project 1 - High Speed Waveguide UTC Photodetector, I-V Curve

Michael Benker

ECE530 – Advanced Electronics/Optoelectronics
UNIVERSITY OF MASSACHUSETTS DARTMOUTH

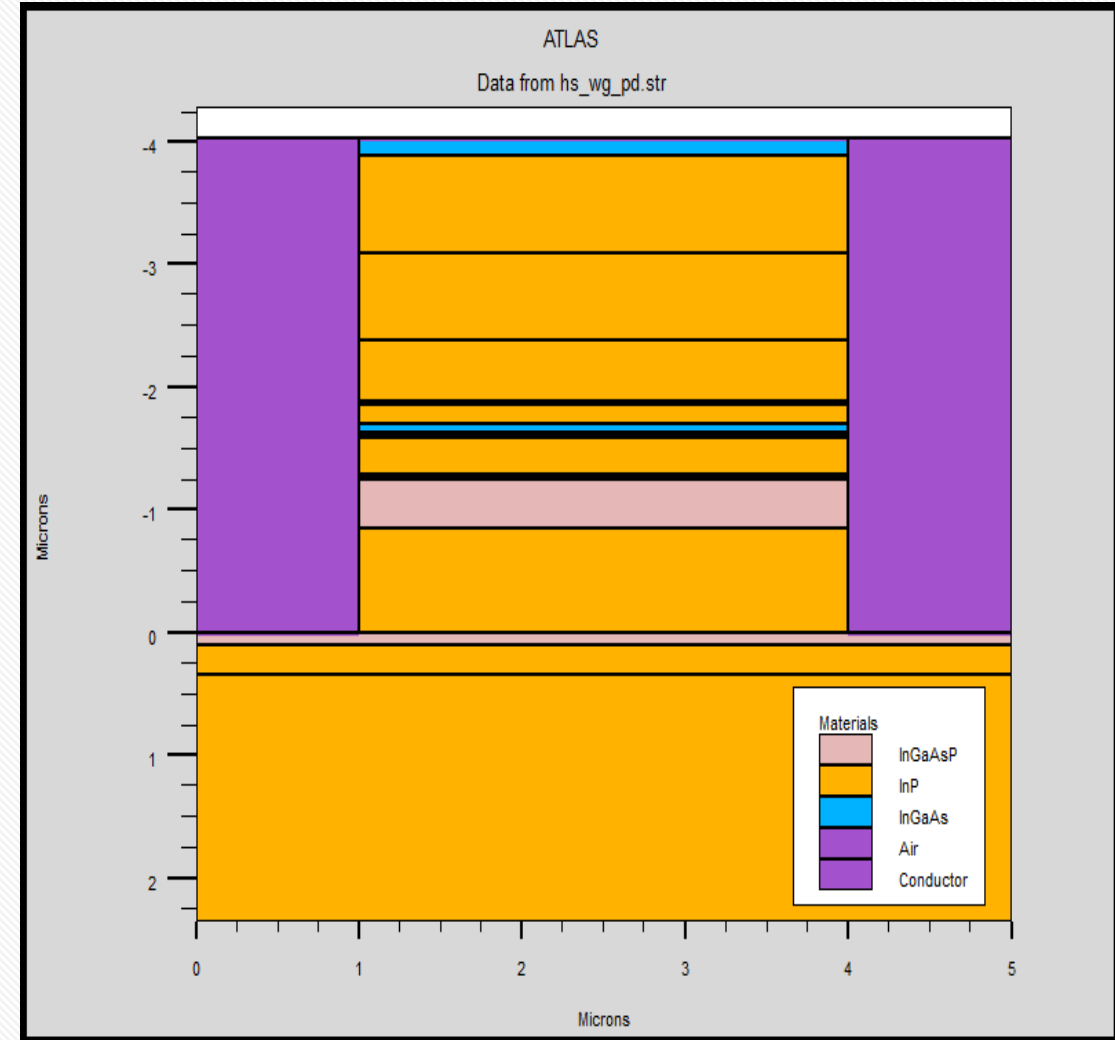
DESIGN SPECIFICATIONS:

Construct an Atlas model for a waveguide UTC photodetector. The P contact is on top of layer R5, and N contact is on layer 16.

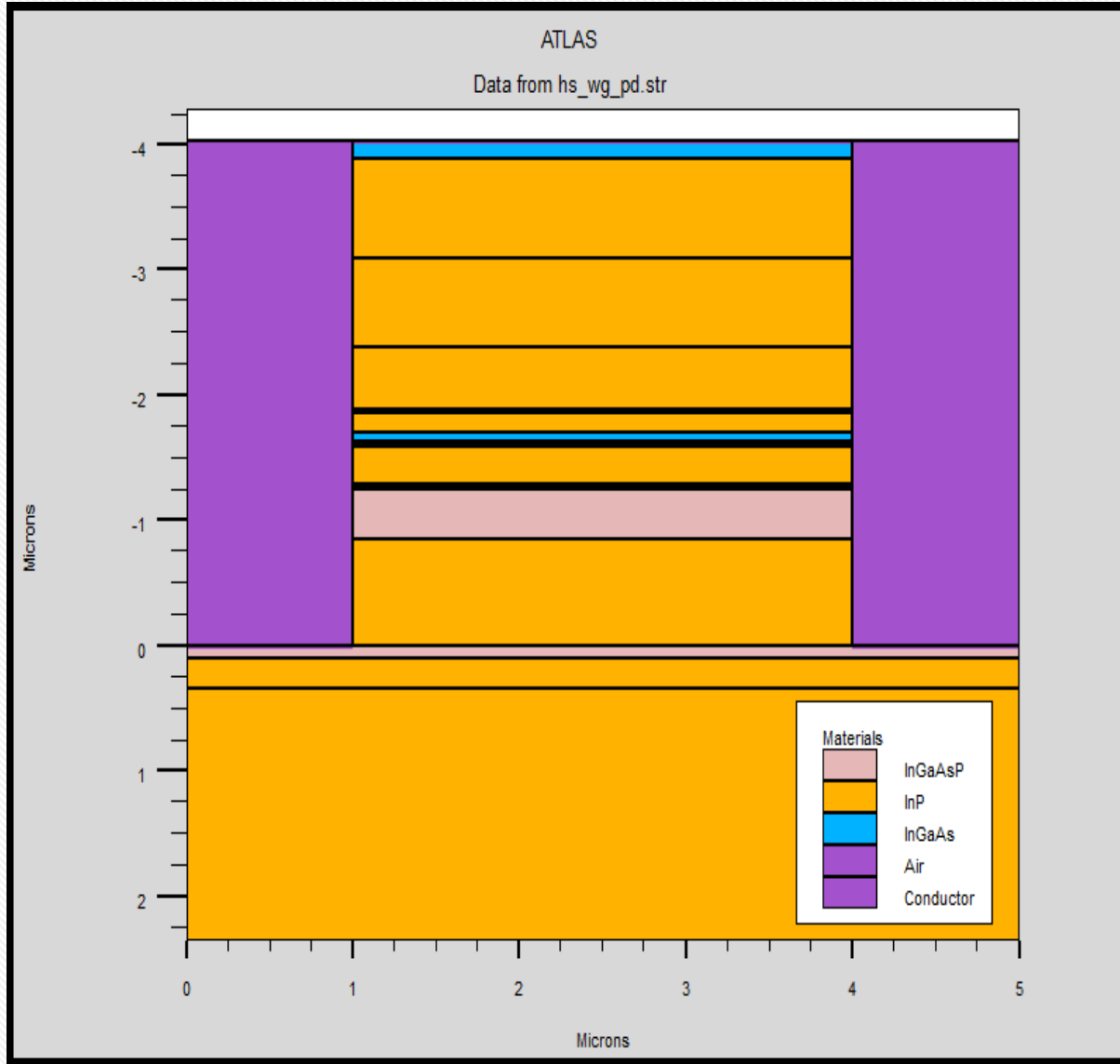
The PIN diode's ridge width is 3 microns.

Please find:

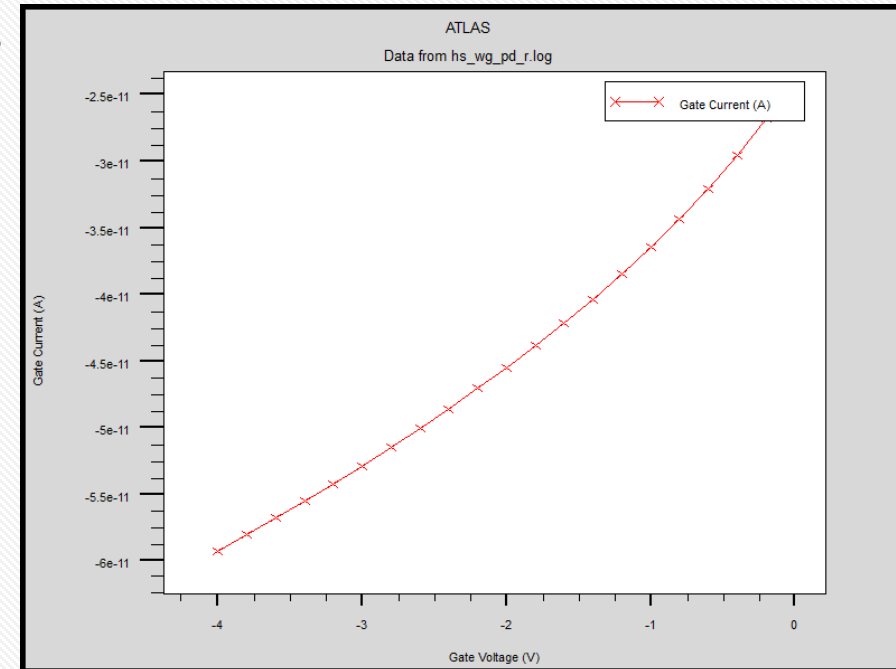
The IV curve of the photodetector (both reverse biased and forward bias)



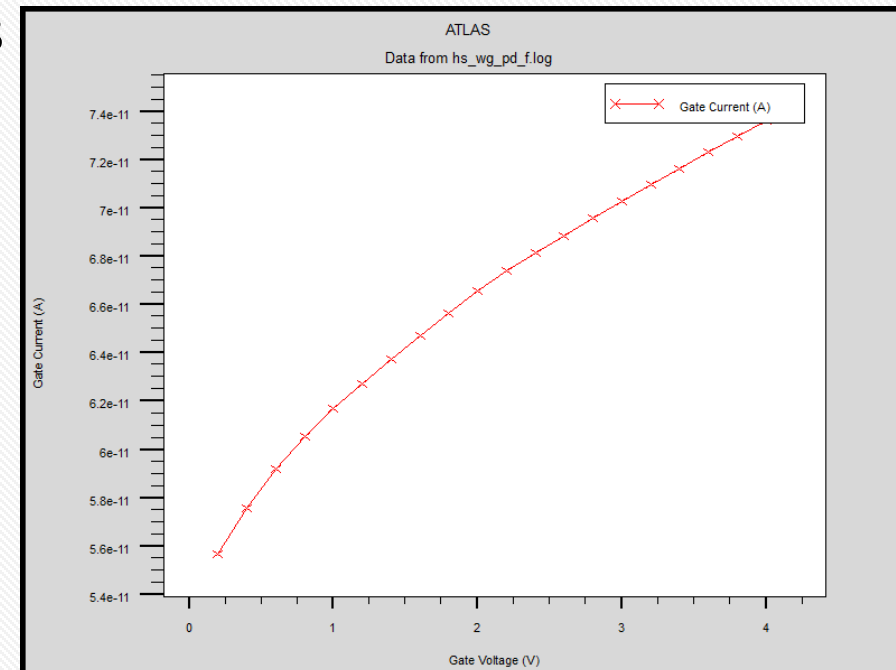
Simulation Results



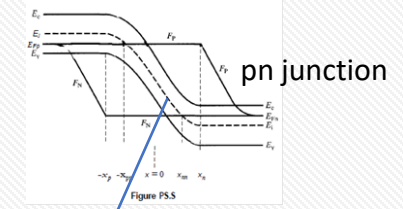
Negative Bias



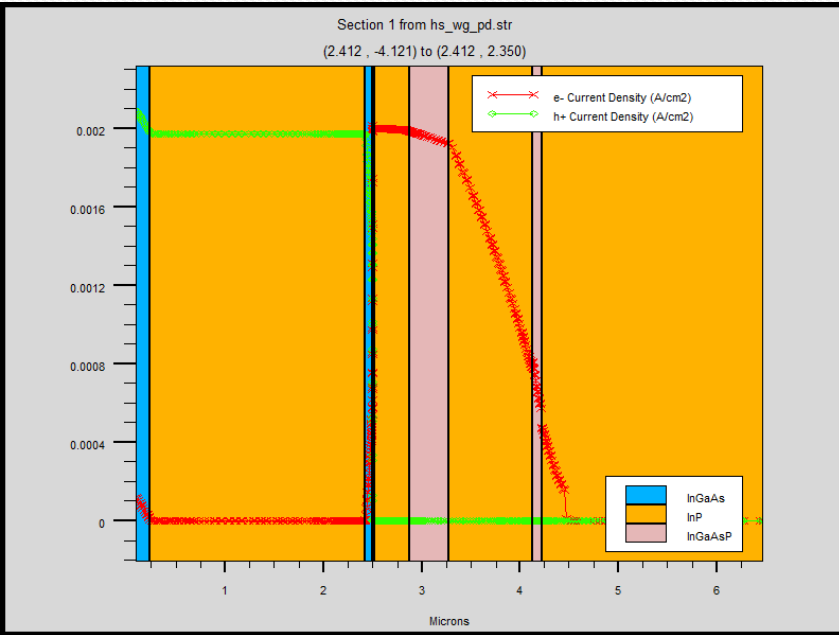
Positive Bias



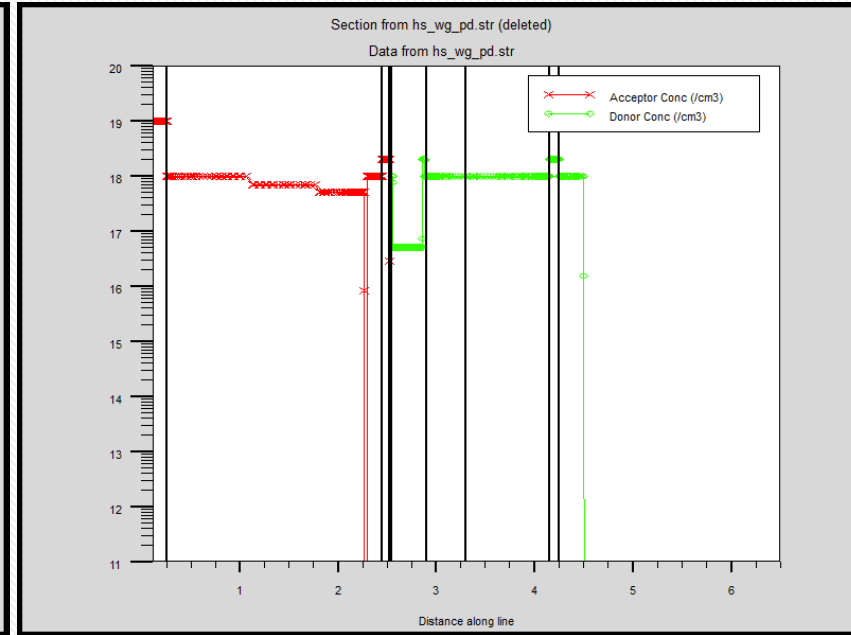
Other Results – Middle Cross Section



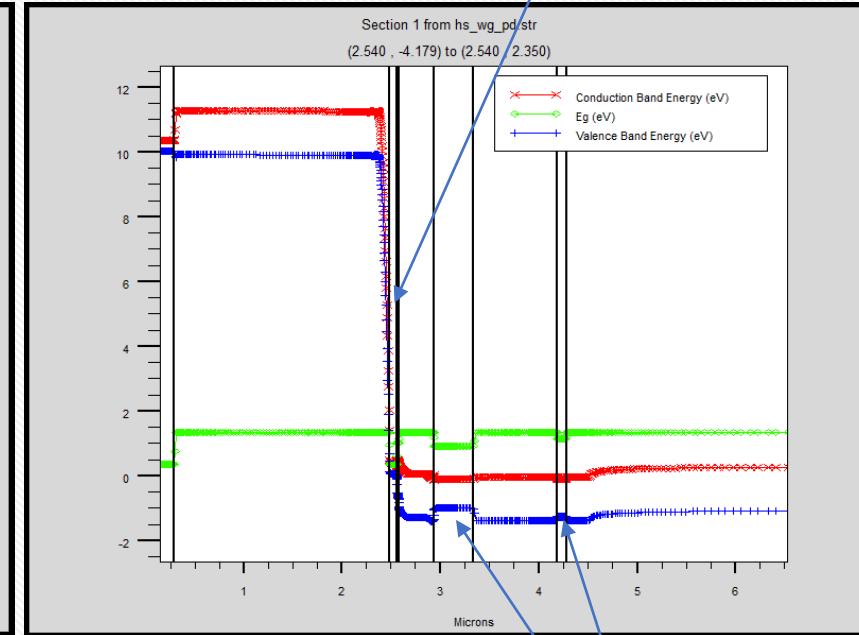
Electron & Hole Current Densities



Donor & Acceptor Concentrations



Bandgap & Conduction, Valence Bands



Current Density in a p-n junction (page 33):

$$J = q \left[\frac{D_n n_{p0}}{L_n} + \frac{D_p p_{n0}}{L_p} \right] \left[\exp \left(\frac{qV_A}{kT} \right) - 1 \right]$$

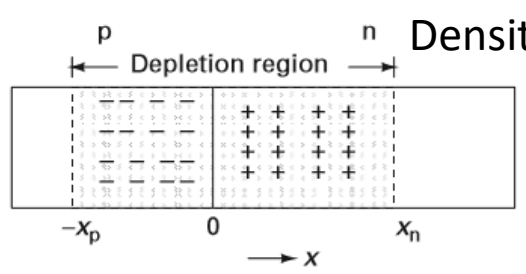
Electron, Hole Concentrations:

$$n_0 = N_c \exp \left(\frac{-(E_c - E_F)}{kT} \right)$$

$$p_0 = N_v \exp \left(\frac{-(E_F - E_v)}{kT} \right)$$

Depletion layer width (page 33):

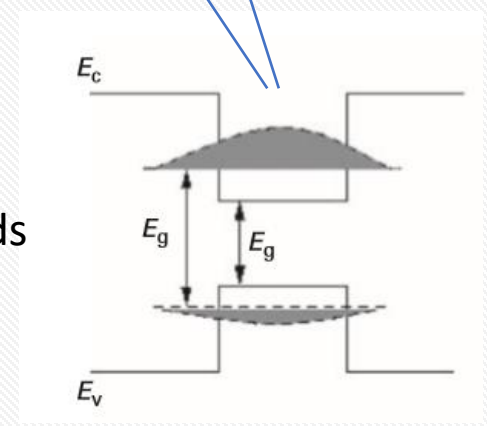
$$W = \sqrt{\frac{2\epsilon_s}{q} \left(\frac{N_D + N_A}{N_A N_D} \right) (V_{bi} \mp V_A)}$$



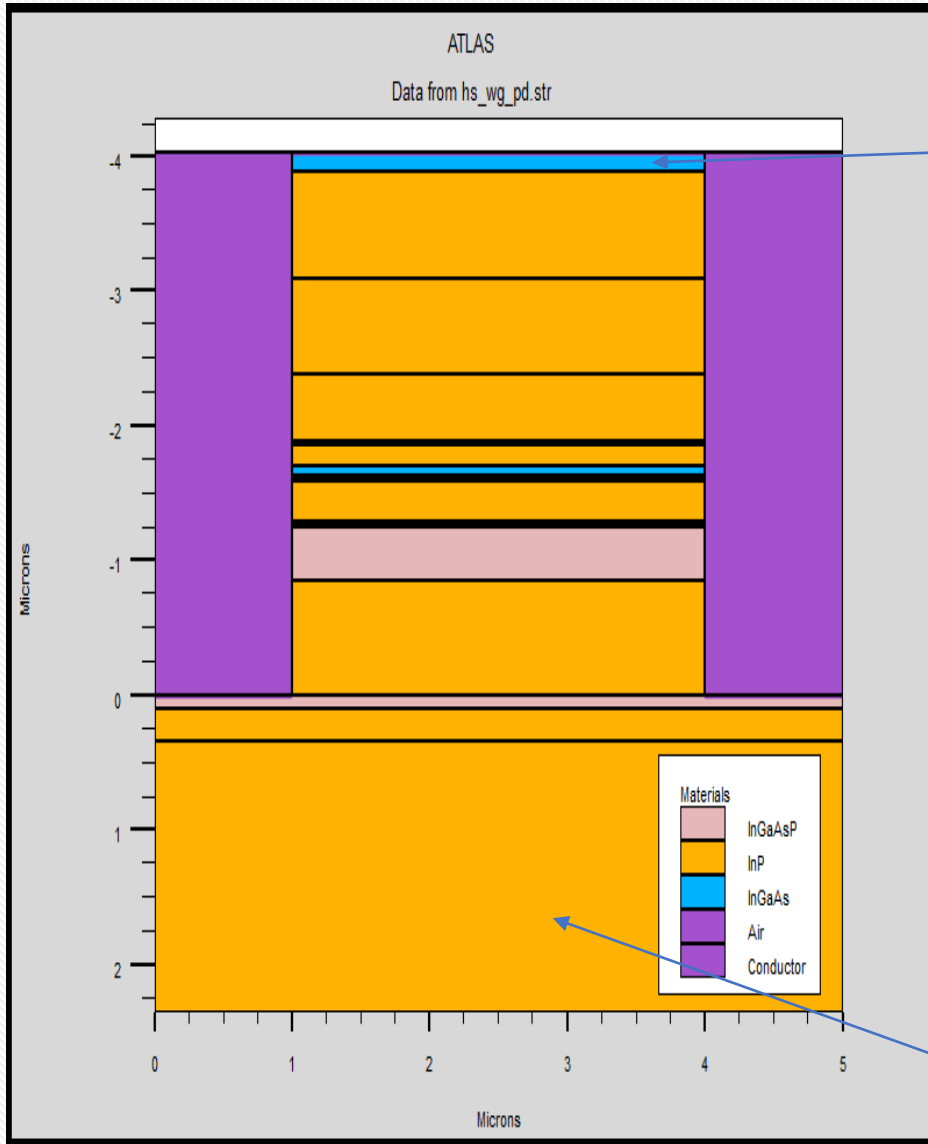
Density of States: Conduction & Valence Bands

$$g_c(E) = \frac{m_n^* \sqrt{2m_n^*(E - E_c)}}{\pi^2 \hbar^3}, \quad E \geq E_c$$

$$g_v(E) = \frac{m_p^* \sqrt{2m_p^*(E_v - E)}}{\pi^2 \hbar^3}, \quad E \leq E_v$$



Structure & Compositions



Top down layer structure:

| | | | | |
|-----|--------|---------|--|---|
| R5 | 1500A | InGaAs | Zn: >1e19 | } P-ohmic contact layer/p-cladding |
| R4 | 8000A | InP | Zn: 1e18 | |
| R3 | 7000A | InP | Zn: 7e17 | |
| R2 | 5000A | InP | Zn: 5e17.....R: regrown layers | } <i>Gradual doping</i> |
| R1 | 300A | InP | UID (unintentionally doped) | |
| 1. | 1500A | InP | Zn: 1e18 | } <i>light absorber</i> |
| 2. | 750A | InGaAs | Zn: 2e18..... | |
| 3. | 80A | InGaAs | | |
| 4. | 160A | 1.24Q | | |
| 5. | 60A | InP | | } UTC photodetector layers |
| 6. | 70A | InP | Si: 1e18.....cleave layer – highly doped | |
| 7. | 3000A | InP | Si: 5e16.....lightly doped | |
| 8. | 250A | InP | Si: 2e18 | } MQW waveguide |
| 9. | 150A | Barrier | Si: 5e17 | |
| 10. | 150A | InP | Si: 1e18 | } N-ohmic contact layer |
| 11. | 800A | Barrier | Si: 1e18 | |
| 12. | 4000A | 1.3Q | Si: 1e18 | |
| 14. | 800A | Barrier | Si: 1e18 | |
| 15. | 8500A | InP | Si: 1e18 | |
| 16. | 1000A | 1.1Q | Si: 2e18 | |
| 17. | 2500A | InP | Si: 1e18 | |
| 18. | 20000A | InP | UID | |

Structure & Compositions

Compositions (x,y):

$\text{In}_x\text{Ga}_{1-x}\text{As}$ ($x = 0.532$) $\text{In}_{0.532}\text{Ga}_{0.468}\text{As}$

1.24Q
Lattice matchd (to InP) InGaAsP with bandgap corresponding to 1.24 micron photon wavelength

1.1Q
Lattice matchd (to InP) InGaAsP with bandgap corresponding to 1.1 micron photon wavelength

1.3Q
Lattice matchd (to InP) InGaAsP with bandgap corresponding to 1.3 micron photon wavelength

Barrier $\text{In}_{0.8}\text{Ga}_{0.2}\text{As}_{0.44}\text{P}_{0.56}$

Zn : P-dopant
Si : n-dopant

Lattice matching:
values approximated using experimental data from publication (see reference).

| $\text{In}_{1-x}\text{Ga}_x\text{As}_y\text{P}_{1-y}$ lattice-matched to InP | | |
|--|------|------|
| λ (μm) | X | Y |
| 1.1 | 0.15 | 0.3 |
| 1.24 | 0.25 | 0.5 |
| 1.3 | 0.3 | 0.65 |

Values of band gap near transition energies, wavelengths, material and lattice mismatch of the grown samples

| Sample | Material | PL energy [eV] | PL Wavelength [nm] | Thickness [nm] | Lattice mismatch [ppm] | x composition | y composition |
|--------|----------|----------------|--------------------|----------------|------------------------|---------------|---------------|
| A | InGaAs | 0.737 | 1682 | 510 | -120 | 0.46 | 1 |
| B | InGaAsP | 0.799 | 1550 | 425 | -100 | 0.42 | 0.90 |
| C | InGaAsP | 0.857 | 1446 | 490 | -250 | 0.38 | 0.79 |
| D | InGaAsP | 0.910 | 1363 | 495 | + 1800 | 0.32 | 0.69 |
| E | InGaAsP | 1.062 | 1168 | 510 | -740 | 0.19 | 0.42 |
| F | InGaAsP | 1.170 | 1059 | 505 | -190 | 0.11 | 0.24 |
| G | InP | 1.346 | 921 | 505 | 0 | 0 | 0 |

[Sten Seifert and Patrick Runge, "Revised refractive index and absorption of \$\text{In}_{1-x}\text{Ga}_x\text{As}_y\text{P}_{1-y}\$ lattice-matched to InP in transparent and absorption IR-region," Opt. Mater. Express 6, 629-639 \(2016\)](#)

```
go atlas

mesh auto
x.m l=0 Spac=0.1
x.m l=1 Spac=0.1
x.m l=4 Spac=0.1
x.m l=5 Spac =0.1

#n region
#1.1Q
region bottom thick = 0.1 material = InGaAsP NY = 10 donor = 2e18 x.comp=0.15 y.comp=0.3
region bottom thick = 0.25 material = InP NY = 10 donor = 1e18
region bottom thick = 2.0 material = InP NY = 10

#waveguide
region top thick = 0.85 material = InP NY = 10 donor = 1e18
region top thick = 0.08 material = InGaAsP NY = 10 donor = 1e18 xcomp=0.2 y.comp=0.44
#1.3Q
region top thick = 0.4 material = InGaAsP NY = 10 donor = 1e18 x.comp=0.3 y.comp=0.65
region top thick = 0.08 material = InGaAsP NY = 10 donor = 1e18 xcomp=0.2 y.comp=0.44

#field terminator
region top thick = 0.015 material = InP NY = 10 donor = 1e18
region top thick = 0.015 material = InGaAsP NY = 10 donor = 5e17 xcomp=0.2 y.comp=0.44

#collector
region top thick = 0.025 material = InP NY = 10 donor = 2e18
region top thick = 0.3 material = InP NY = 10 donor = 5e16
region top thick = 0.007 material = InP NY = 10 donor = 1e18

#band smoothing
region top thick = 0.006 material = InP NY = 10
#1.24Q
region top thick = 0.016 material = InGaAsP NY = 10 x.comp=0.25 y.comp=0.5

region top thick = 0.008 material = InGaAs NY = 10
region top thick = 0.075 material = InGaAs NY = 10 acceptor = 2e18

#p-cladding
region top thick = 0.15 material = InP NY = 10 acceptor = 1e18

#regrowth layers
region top thick = 0.03 material = InP NY = 10
region top thick = 0.5 material = InP NY = 10 acceptor = 5e17
region top thick = 0.7 material = InP NY = 10 acceptor = 7e17
region top thick = 0.8 material = InP NY = 10 acceptor = 1e18

#p-contact
region top thick = 0.15 material = InGaAs NY = 10 acceptor = 1e19
```

```
#etch
region mat = air x.min = 0 x.max = 1 y.max = 0
region mat = air x.min = 4 x.max = 5 y.max = 0

#electrode
electrode name=gate x.min = 1 x.max = 4 top
electrode name=np x.min=0 x.max=1 y.max = 0 y.min = 0
electrode name=np x.min=4 x.max=5 y.max = 0 y.min = 0

contact name=gate resistance = 50

#Materials
material material=InGaAsP taun0=20.e-9 taup0=33e-9 \
align=0.4 real.index=3.4 imag.index=0

material material=InGaAs taun0=0.7e-9 taup0=33e-9 \
real.index=3.43 imag.index=0.2

material material=InP taun0=2e-9 taup0=33e-9 \
align=0.4 real.index=3.17 imag.index=0

#model
models fldmob srh optx fermidirac conmob print EVSATMOD=1

mobility material = InP mun=4917.0 mup=150.0 vsatn = 2.6e7 vsatp = 0.66e7 ecritn=11e3 ecritp=4e3 gamman=4 gammap=1
mobility material = InGaAs mun=11599.0 mup=331.0 vsatn = 2.5e7 vsatp=0.5e7 ecritn=3e3 ecritp=4e3 gamman=4 gammap=1
mobility material = InGaAsP mun=4600.0 mup=150.0 vsatn = 2.68e7 vsatp=0.6e7 ecritn=6e3 ecritp=4e3 gamman=4 gammap=1

#solving
solve init outf = sol_hswgpd.str
load inf = sol_hswgpd.str

LOG outf=hs_wg_pd_f.log

solve vgate=0.2 vstep=0.2 vfinal=4 name="gate"
tonyplot hs_wg_pd_f.log

log off

solve init outf = sol_hswgpd.str
load inf = sol_hswgpd.str
LOG outf=hs_wg_pd_r.log

solve vgate=-0.2 vstep=-0.2 vfinal=-4 name="gate"

tonyplot hs_wg_pd_r.log

log off

output band.param photogen opt.intens con.band val.band

save outf=hs_wg_pd.str

tonyplot hs_wg_pd.str

#tonyplot sol_hswgpd.str

quit
```